

Title (en)

PHOTOACID GENERATORS IN PHOTORESIST COMPOSITIONS FOR MICROLITHOGRAPHY

Title (de)

FOTOSÄURE ERZEUGENDE SUBSTANZEN IN PHOTORESISTZUSAMMENSETZUNGEN FÜR DIE MIKROLITHOGRAPHIE

Title (fr)

GENERATEURS PHOTOACIDES UTILISES DANS DES COMPOSITIONS DE PHOTORESIST POUR LA MICROLITHOGRAPHIE

Publication

EP 1332406 A2 20030806 (EN)

Application

EP 01990140 A 20011031

Priority

- US 0148006 W 20011031
- US 24739300 P 20001109

Abstract (en)

[origin: WO0239186A2] A photoresist composition having a polymeric binder; and a photoactive component selected from the group consisting of (1) hydroxamic acid sulfonyl esters containing a perfluoroalkyl group containing at least five carbon atoms; (2) S-perfluoroalkyldibenzothiophenium salts; and (3) S-perfluoroalkyldiarylsulfonium salts. These photoactive components are compatible with the polymeric binders that are useful for imaging with exposure to light at the relatively shorter wavelengths, such as 157 nm.

IPC 1-7

G03F 7/004

IPC 8 full level

G03F 7/004 (2006.01); **G03F 7/039** (2006.01); **H01L 21/027** (2006.01); **G03F 7/038** (2006.01)

CPC (source: EP KR)

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Citation (search report)

See references of WO 0239186A2

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